



Docket No. 740107-135

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of: )  
Nobuo SHIMAZU et al. ) Group Art Unit: 2881  
Serial No. 09/732,927 ) Examiner: K. Fernandez  
Filed: December 11, 2000 )  
For: MANUFACTURING METHOD OF )  
MASK FOR ELECTRON BEAM )  
PROXIMITY EXPOSURE AND MASK )

**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on November 25, 2002.

K.M. McManus  
K.M. McManus

**AMENDMENT**

Commissioner for Patents  
Washington, D.C. 20231

Sir:

The following is presented in response to the Office Action mailed July 3, 2002, in connection with the above captioned patent application.

**In the Claims:**

Please amend the claims as follows:

1. A method for manufacturing an object mask which is used in an electron beam proximity exposure apparatus comprising an electron beam source which emits a collimated electron beam, the object mask having an aperture which is arranged on a path of the electron beam, and a stage which holds and moves an object, wherein the object mask is arranged in proximity to a surface of the object and a pattern corresponding to the aperture of the object mask is exposed on the surface of the object with the electron beam having passed through the aperture, the method comprising the steps of:

manufacturing a master mask having an aperture of a pattern identical with the object mask; and

manufacturing a child mask by exposing an aperture pattern identical with the master mask by using the master mask as the object mask in an electron beam proximity exposure

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